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CHEM, LTD. [KR/KR]; LG Twin Tower, Yoido-dong 20,
Youngdungpo-ku, Seoul 150-721 (KR).

(72) Inventors; and

(75) Inventors/Applicants (for US only): KANG, Jung-Won
[KR/KR]; 2-306 Geukdong apt., Hagye-dong, Nowon-gu,
Seoul 139-230 (KR). KO, Min-Jin [KR/KR]; 5-304
LG employee's apt., Doryong-dong, Yuseong-gu, Dae-
jeon-city 305-340 (KR). SHIN, Dong-Seok [KR/KR];
48-207 Siyoung apt., Sincheon-dong, Songpa-gu, Seoul
138-240 (KR). KANG, Gwi-Gwon [KR/KR]; 1036-19
Hwagok 3-dong, Gangseo-gu, Seoul 157-013 (KR).
MOON, Myung-Sun [KR/KR]; 105-804 Saemme-
ori apt., Dunsan-dong, Seo-gu, Daejeon-city 302-120
(KR). NAM, Hae-Young [KR/KR]; 103-407 Boseong
apt., Bokdae 2-dong, Heungdeok-gu, Cheongju-city,
Chungcheongbuk-do 361-272 (KR). CHOI, Bum-Gyu
[KR/KR]; 311-204 Songganggreen apt., Songgang-dong,
Yuseong-gu, Daejeon-city 305-751 (KR). KIM,Young-Duk [KR/KR]; 101-904 Cheonggu apt., Jeon-
min-dong, Yuseong-gu, Daejeon-city 305-390 (KR).
KIM, Byung-Ro [KR/KR]; 406-406 Expo apt., Jeon-
min-dong, Yuseong-gu, Daejeon-city 305-762 (KR).
KWON, Won-Jong [KR/KR]; 106-705 Sejong apt.,
Jeonmin-dong, Yuseong-gu, Daejeon-city 305-728 (KR).
PARK, Sang-Min [KR/KR]; 110-402 Hyundai apt.,
Yucheon 2-dong, Jung-gu, Daejeon-city 301-757 (KR).(74) Agent: YOU ME PATENT & LAW FIRM; Teheran
Bldg., 825-33, Yoksam-dong, Kangnam-ku, Seoul 135-080
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ning of each regular issue of the PCT Gazette.

(54) Title: ORGANIC SILICATE POLYMER AND INSULATION FILM COMPRISING THE SAME

(57) Abstract: The present invention relates to an organic silicate polymer prepared by mixing silane compound with organic sol-
vent to prepare a first mixture, and hydrolyzing and condensing the first mixture by adding water and catalyst, the first mixture being
selected from a group consisting of oxidized hydrosilane, cyclic siloxane, a second mixture of oxidized hydrosilane and silane or
silane oligomer, and a third mixture of cyclic siloxane and silane or silane oligomer, a composition for forming an insulation film of
semiconductor devices prepared by using the organic silicate polymer, a method for preparing an insulation film using the compo-
sition, and a semiconductor device comprising the insulation film.

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